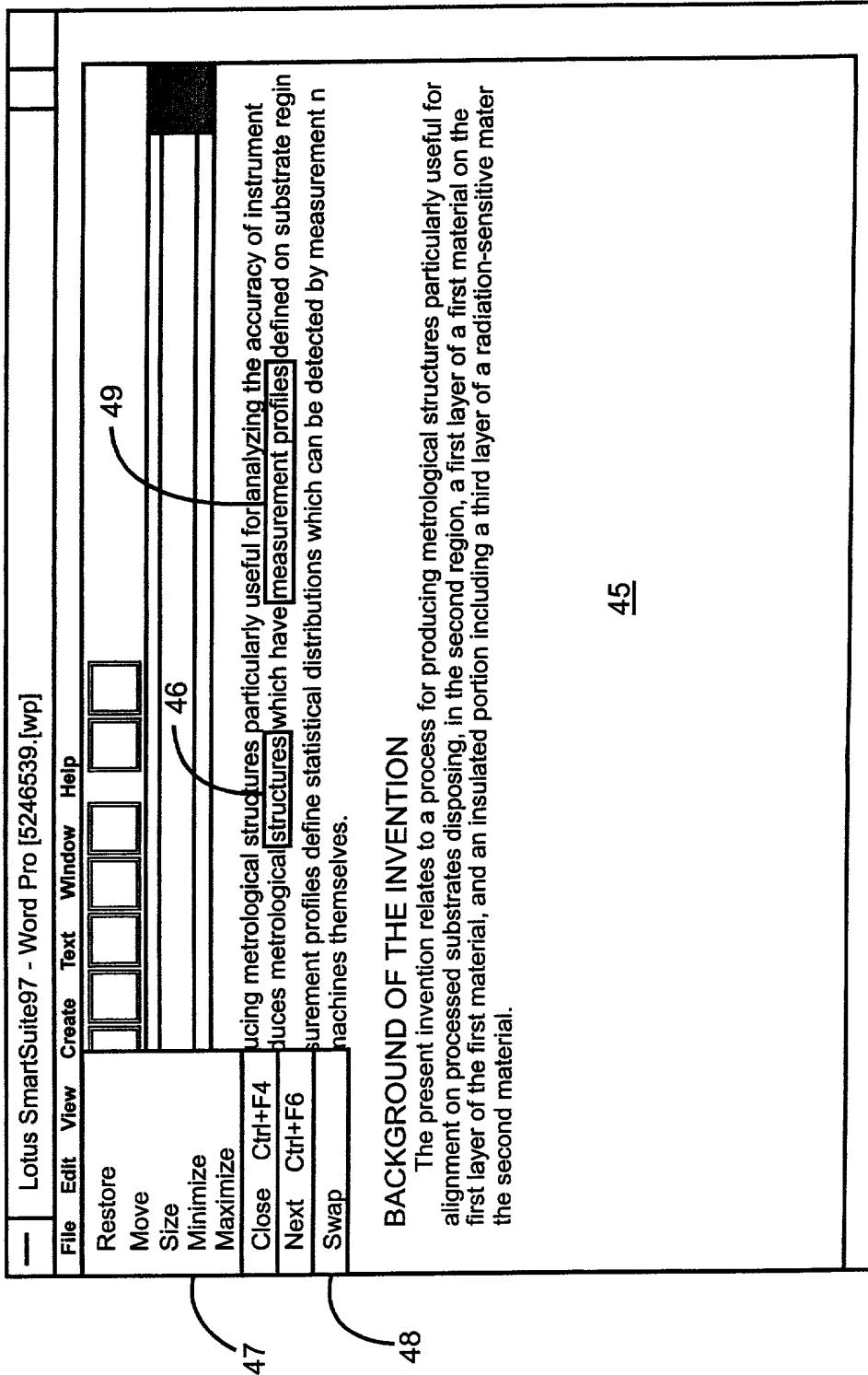


FIG. 1

FIG. 2



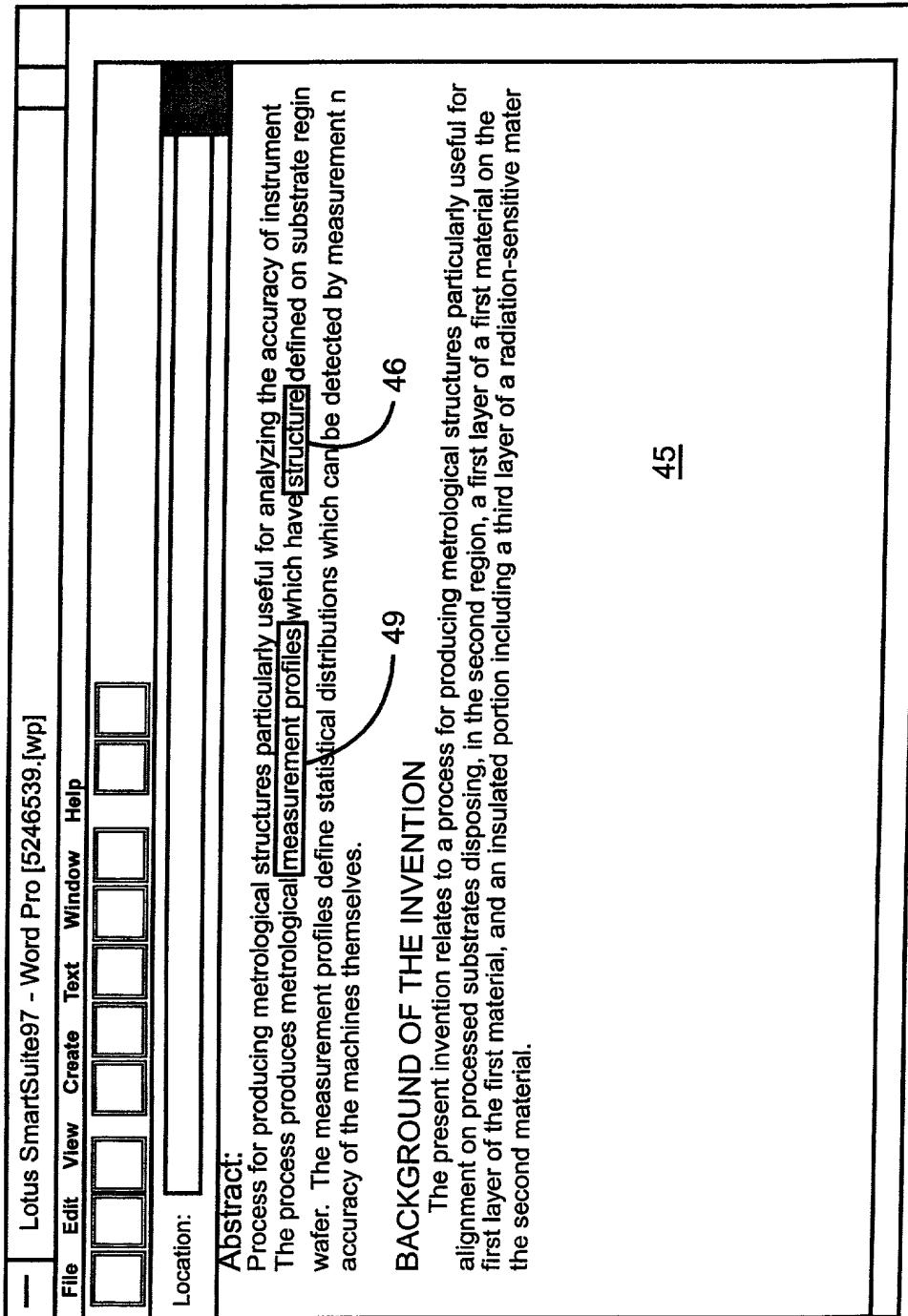
BACKGROUND OF THE INVENTION

The present invention relates to a process for producing metrological structures particularly useful for alignment on processed substrates disposing, in the second region, a first layer of a first material on the first layer of the first material, and an insulated portion including a third layer of a radiation-sensitive material the second material.

45

48

FIG. 3



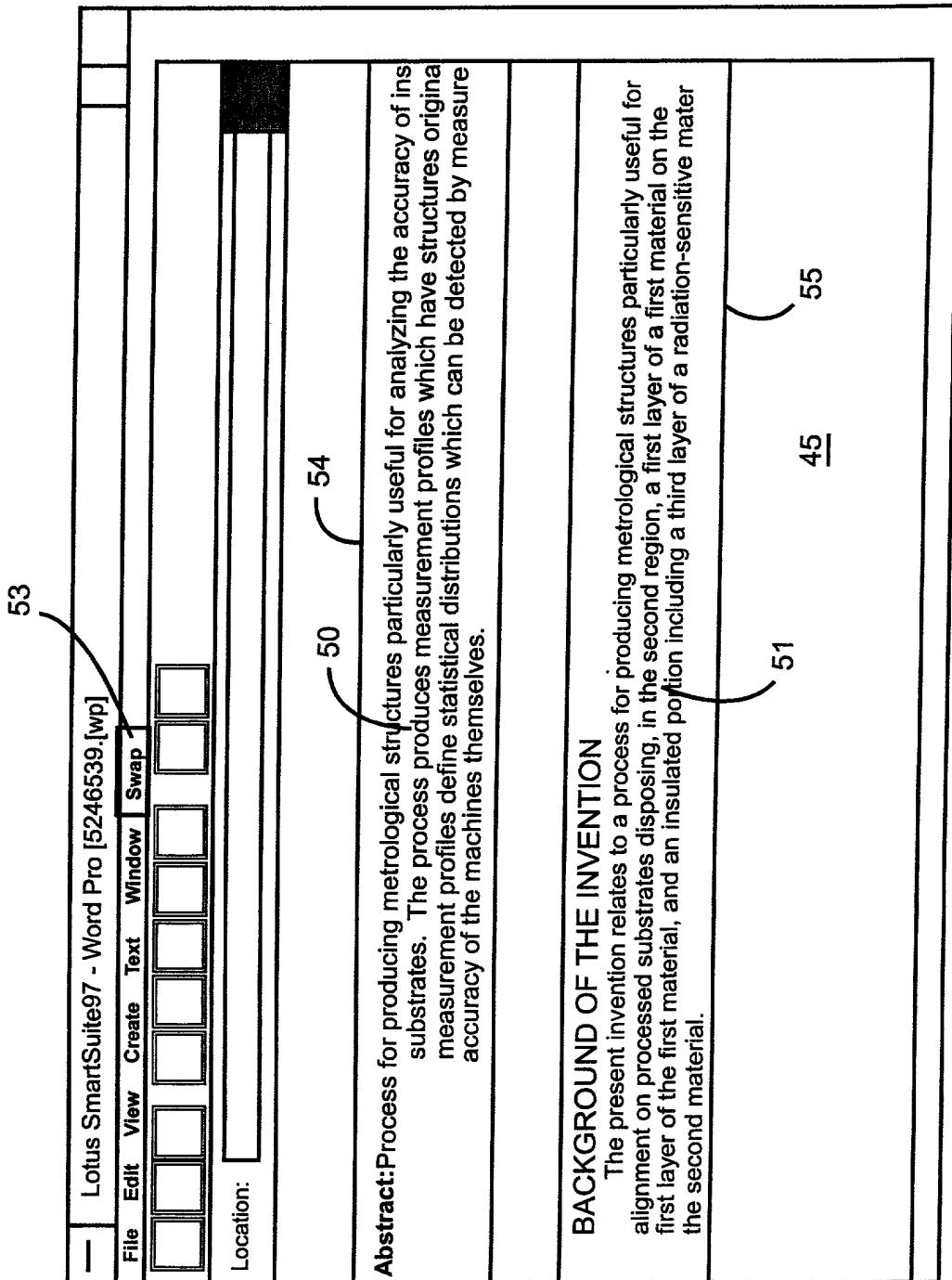
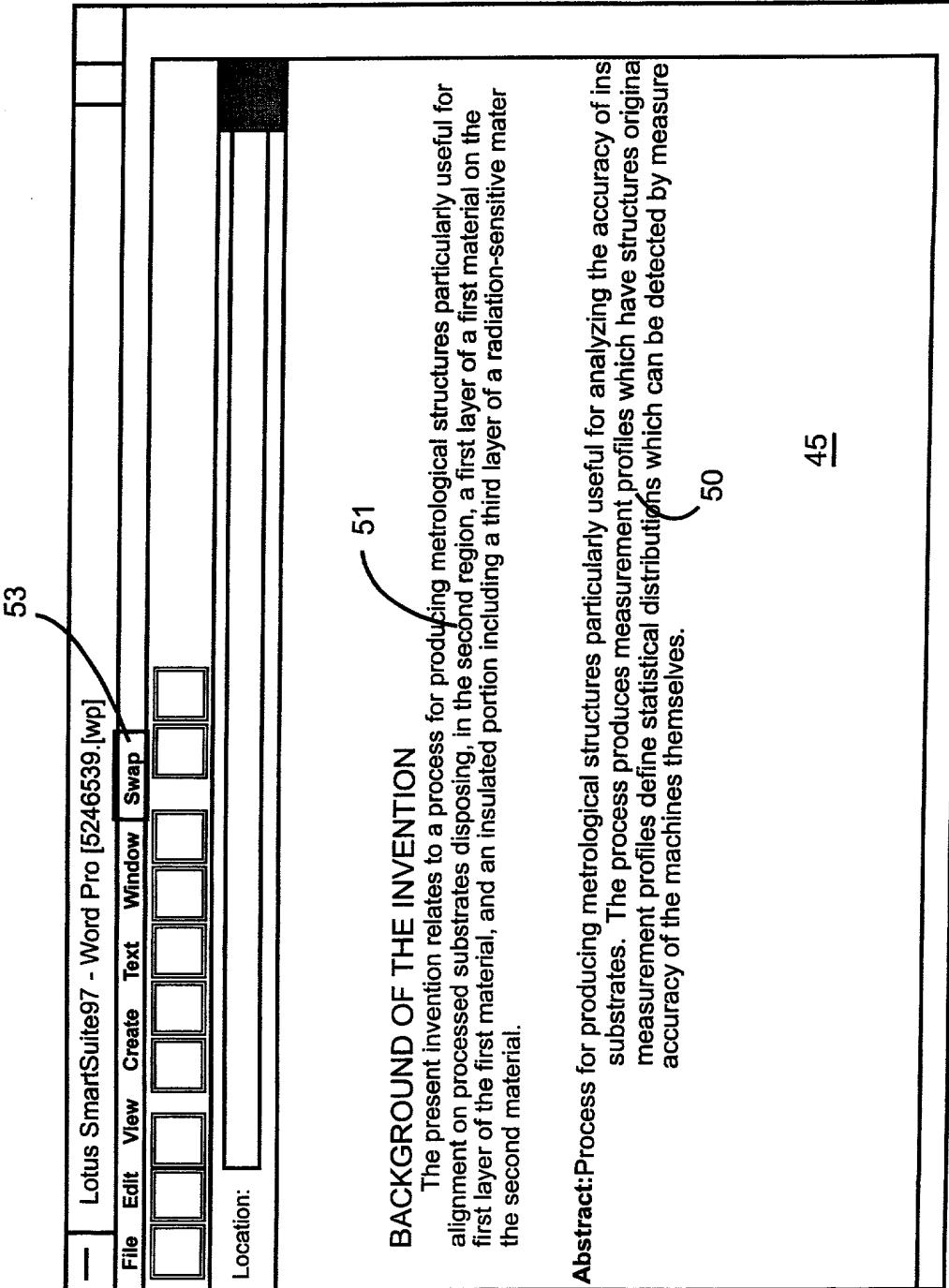
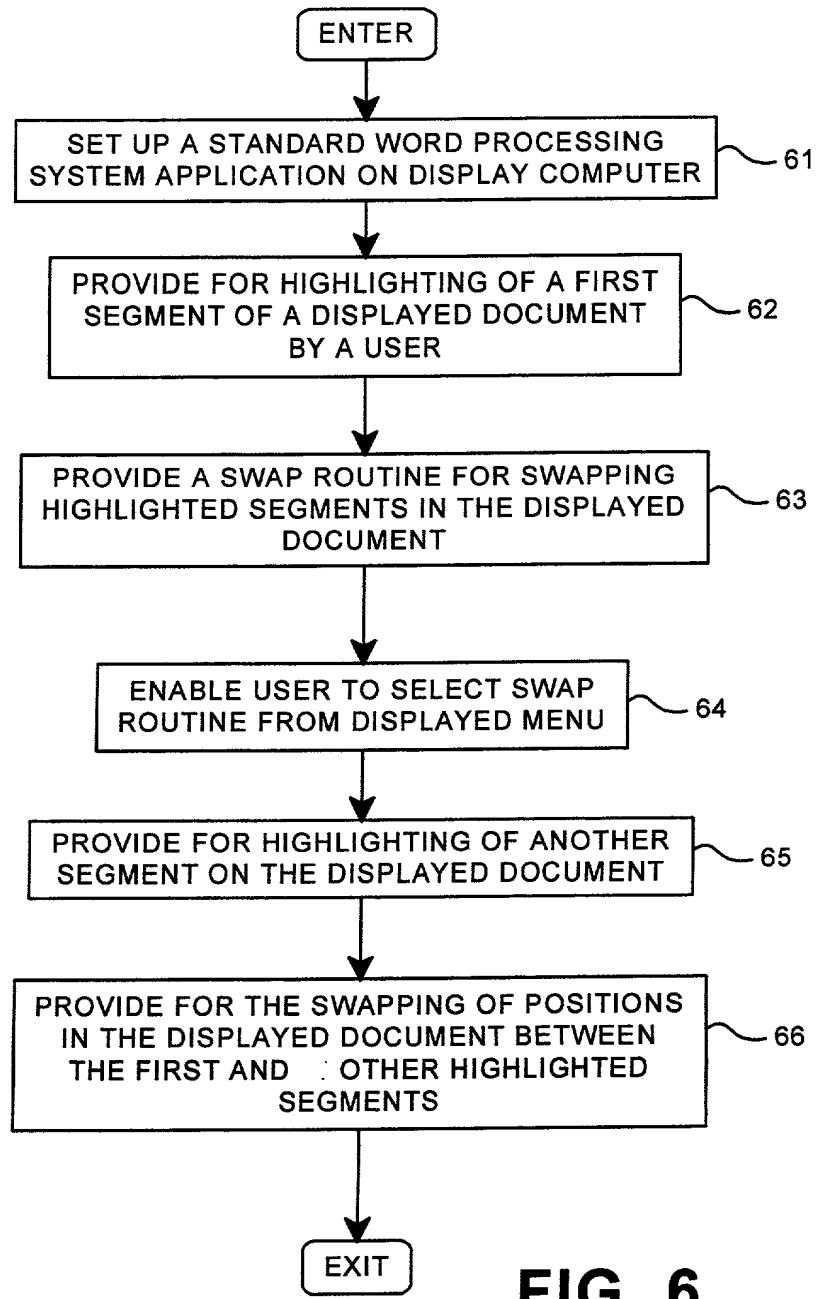
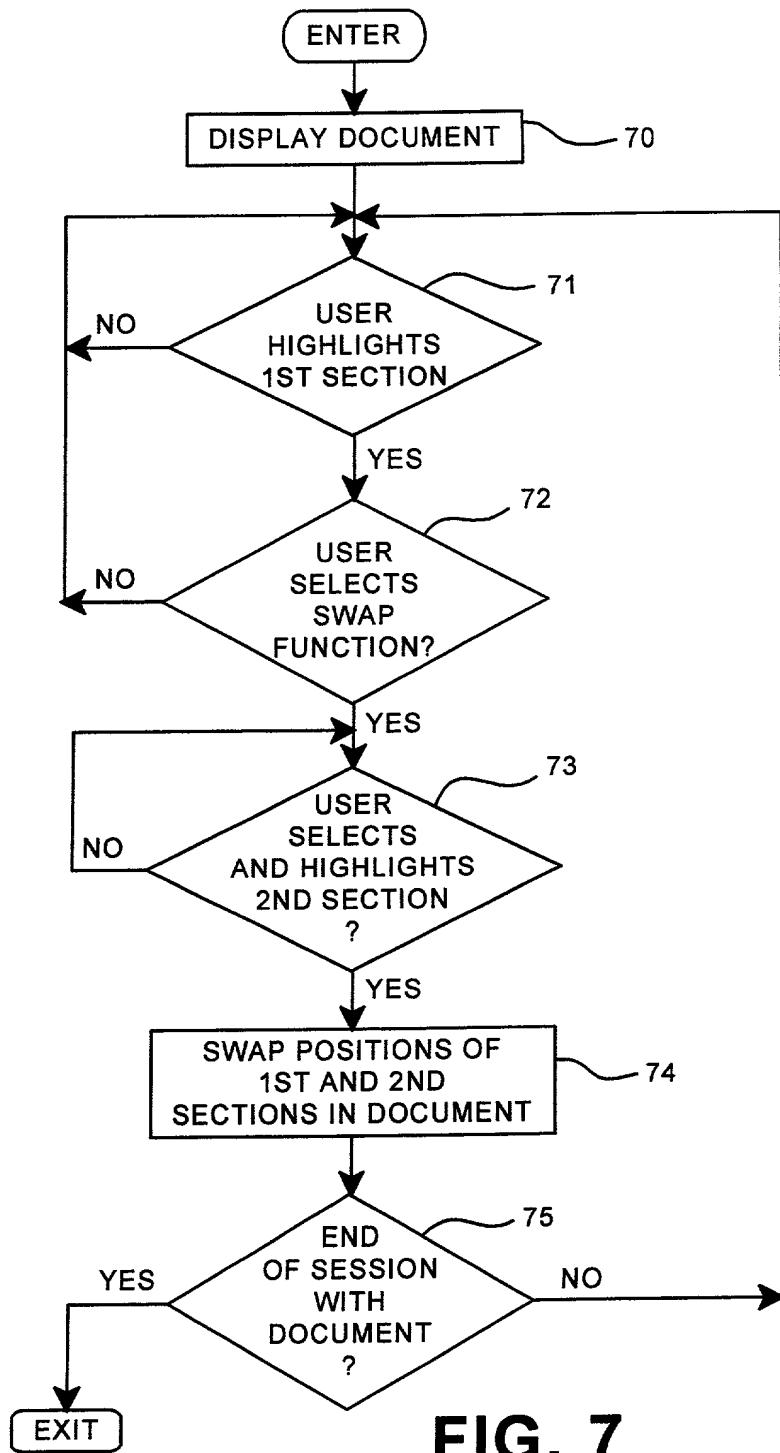


FIG. 4

FIG. 5



**FIG. 6**

**FIG. 7**